

Appl. No. 10/661,793
Amdt. dated 04/01/2008
Response to Office action of 01/03/2008

Attorney Docket No.: TS01-1037
N1085-90149

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Amendments to the Claims:

APR 01 2008

This listing of claims will replace all prior versions and listings of claims in the application:

1 1.-7. (Cancelled)

1 8. (Currently Amended) A system for creation of an opening of controllable format
2 through a layer of insulation material, comprising:

3 means for creating an opening through a layer of etch resist material provided
4 over the surface of a layer of insulating material having been deposited over the surface
5 of a substrate;

6 means for measuring an obtained critical dimension measurement of said
7 opening created through said layer of etch resist material;

8 means, including a feedback mechanism, for assuring that the obtained critical
9 dimension measurement of said opening created through said layer of etch resist
10 material is within design specification, said feedback mechanism communicating with
11 said means for creating an opening through a layer of etch resist material to control said
12 critical dimension measurement of said opening by implementing corrections in said
13 means for creating an opening through a layer of etch resist material;

14 means for creating an opening through said layer of insulation material, whereby
15 a diameter of said opening through said layer of insulation material is dependent on a
16 diameter of said opening created through said layer of etch resist material; and

17 means, including a feedback mechanism, for assuring that said opening created
18 through said layer of insulation material is within design specification.

1 9. (Previously Presented) The system of claim 8, said means, including a feedback
2 mechanism, for assuring that an obtained critical dimension measurement of said
3 opening created through said layer of etch resist material is within design specification
4 comprising:

Appl. No. 10/661,793
Amdt. dated 04/01/2008
Response to Office action of 01/03/2008

Attorney Docket No.: TS01-1037
N1085-90149

means for linking to a software supervisory function, thereby including data transmission functions;

means for linking to a software function equally being linked to a software supervisory function, thereby including data transmission functions;

means for data manipulating capabilities, thereby including manipulating interdependent data;

means for interfacing with semiconductor equipment, thereby including equipment functioning in a supporting role to said semiconductor equipment; and

means for creating instructions for said semiconductor equipment, thereby including equipment functioning in a supporting role to said semiconductor equipment.

10. (Original) The system of claim 8, said means for assuring that said opening created through said layer of insulation material is within design specification comprising:

means for linking to a software supervisory function, thereby including data transmission functions;

means for linking to a software function equally being linked to a software supervisory function, thereby including data transmission functions;

means for data manipulating capabilities, thereby including manipulating interdependent data;

means for interfacing with semiconductor equipment, thereby including equipment functioning in a supporting role to said semiconductor equipment; and

means for creating instructions for said semiconductor equipment, thereby including equipment functioning in a supporting role to said semiconductor equipment.

11. (Original) The system of claim 8, further comprising means for creating an opening having non-linear sidewalls through a layer of insulation material by applying a high-polymer based etch to the surface of said layer of insulation material.

Appl. No. 10/661,793
Amdt. dated 04/01/2008
Response to Office action of 01/03/2008

Attorney Docket No.: TS01-1037
N1085-90149

12. (Previously Presented) A system for creation of an opening of controllable format through a layer of insulation material, comprising:
means for software processing capabilities, said software processing capabilities comprising;
(i) first software processing capabilities being photoresist processing based;
and
(ii) second software processing capabilities being insulating layer etch based;
means for providing a parameter having a first value of After Development Inspection Critical Dimension (ADI CD) to said first software processing capability, said ADI CD being a diameter of an opening being created through a layer of photoresist;
means for evaluating issuance of a first instruction, comprising:
(i) a first instruction having been issued, modifying said first value of ADI CD based on said first instruction, creating a second value of ADI CD; and
(ii) no first instruction having been issued, converting said step of evaluation for a first instruction having been issued into a no-op or void step;
means for coating a layer of photoresist over the surface of said layer of insulation material;
means for developing said layer of photoresist, creating an opening having a diameter of a second value of ADI CD through said layer of photoresist;
means for measuring said second value of ADI CD;
means for determining a first difference between said second value of ADI CD and said first value of ADI CD;
means for creating said first instruction based on said first difference, said first instruction comprising:
(i) continuing processing said substrate, said instruction of continue processing said substrate being indicative of said first difference being less than a first ADI CD inspection limit, said continue processing said substrate proceeding with a subsequently specified step of providing a parameter having a value of said second value ADI CD to said second software processing capability;

Appl. No. 10/661,793
Amdt. dated 04/01/2008
Response to Office action of 01/03/2008

Attorney Docket No.: TS01-1037
N1085-90149

(ii) removing said developed layer of photoresist from the surface of said layer of insulation material, further invoke said step of modifying said first value of ADI CD based on said first instruction, said first value of ADI CD of said modifying taking on the value of said second value of ADI CD, followed by said steps specified herein following said step of evaluating issuance of a first instruction, said instruction of invoke said modifying said first value of ADI CD based on a first instruction being indicative of said first difference being less than a first ADI CD inspection limit;

(iii) discontinuing processing said substrate, said instruction of discontinue processing said substrate being indicative of said first difference being more than a second ADI CD inspection limit, said instruction of discontinue processing said substrate further being indicative of a judgment that processing said wafer must be discontinued;

means for executing said first instruction;

means for providing a parameter having a value of said second value ADI CD to said second software processing capability;

means for first modifying said second value of ADI CD based on an equation, creating a first value of After Etch Inspection Critical Dimension (AEI CD);

means for evaluating issuance of a second instruction, comprising:

(i) a second instruction having been issued, modifying said first value of AEI CD based on said second instruction, creating a second value of AEI CD; and

(ii) no second instruction having been issued, converting said step of evaluation for a second instruction having been issued into a no-op or void step;

means for etching an opening having a diameter of a second value of AEI CD through said layer of insulation;

means for measuring said second value of AEI CD;

means for determining a second difference between said second value of AEI CD and said first value of AEI CD;

means for determining said second instruction based on said second difference, said second instructions comprising:

Appl. No. 10/661,793
Amdt. dated 04/01/2008
Response to Office action of 01/03/2008

Attorney Docket No.: TS01-1037
N1085-90149

(i) continuing processing said substrate, said instruction of continue processing said substrate being indicative of said first difference being less than a first AEI CD inspection limit, said continue processing said substrate resulting in termination of said second software processing, thereby releasing said substrate for additional processing not under control of said first and second software processing capabilities;

(ii) invoking said second modifying said first value of AEI CD based on a second instruction, said first value of said second modifying of AEI CD taking on the value of said second value of AEI CD, followed by said steps specified herein following said step of second modifying said first value of AEI CD based on a second instruction, said instruction of invoke said modifying said first value of AEI CD based on first instructions being indicative of said first difference being less than a first AEI CD inspection limit;

(iii) discontinuing processing said substrate, said instruction of discontinue processing said substrate being indicative of said first difference being more than a second ADI CD inspection limit; and

means for executing said second instruction.

13. (Original) The system of claim 12, said first software processing capabilities comprising:

means for linking to a supervisory software function;

means for accepting first data from and providing first data to said supervisory software function, thereby including data of ADI CD and AEI CD;

means for calculating data, creating first output data, based on first input data and in accordance with a first relationship as embodied in a first equation between said first input data and said first output value for ADI CD based on a first input value of ADI CD;

means for providing to and accepting from photoresist processing equipment data that relate to photoresist processing, thereby including a value of ADI CD;

means for providing to and accepting from photoresist related processing equipment instructions of or relating to performance of operations by said photoresist

Appl. No. 10/661,793
Amdt. dated 04/01/2008
Response to Office action of 01/03/2008

Attorney Docket No.: TS01-1037
N1085-90149

14 related processing equipment, thereby including an instruction to measure a diameter of
15 an opening created through said layer of photoresist, thereby further including receiving
16 first measurement results of a first diameter of a first opening created through said layer
17 of photoresist;

18 means for calculating a first difference between numerical values, thereby
19 included calculating a first difference between a first value of ADI CD and a measured
20 value of ADI CD;

21 means for evaluating results obtained by said calculating a first difference
22 between numerical values; and

23 means for creating first instructions relating to said first software processing
24 capabilities being photoresist processing based, thereby including first instructions of
25 terminating photoresist processing, of continuing photoresist processing or of invoking
26 said function of calculating data, creating output data of said first software processing
27 capabilities.

1 14. (Original) The system of claim 12, said second software processing capabilities
2 comprising:

3 means for linking to said first software processing capabilities;

4 means for accepting second data from and providing second data to said second
5 software processing capabilities, thereby including data of ADI CD and AEI CD;

6 means for calculating data, creating second output data, based on second input
7 data and in accordance with a second relationship as embodied in a second equation
8 between said second input data and said second output data, thereby including
9 calculating a first output value for AEI CD based on a first input value of ADI CD,
10 thereby further including calculating a second output value for AEI CD based on a
11 second input value for AEI CD;

12 means for providing to and accepting from etch processing equipment data that
13 relate to etch processing, thereby including a value of ADI CD, thereby further including
14 a value of AEI CD;

Appl. No. 10/661,793
Amdt. dated 04/01/2008
Response to Office action of 01/03/2008

Attorney Docket No.: TS01-1037
N1085-90149

15 means for providing to and accepting from etch related processing equipment
16 instructions of or relating to performance of operations by said etch related processing
17 equipment, thereby including an instruction to measure a diameter of an opening
18 created through said layer of insulation material, thereby further including receiving first
19 measurement results of a first diameter of a first opening created through said layer of
20 insulation material;

21 means for calculating a second difference between numerical values, thereby
22 included calculating a second difference between a first value of AEI CD and a
23 measured value of AEI CD;

24 means for evaluating results obtained by said calculating a second difference
25 between numerical values; and

26 means for creating second instructions relating to said second software
27 processing capabilities being etch processing based, thereby including second
28 instructions of terminating etch processing, of continuing etch processing or of invoking
29 said function of calculating data, creating output data of said second software
30 processing capabilities.

1 15. (Previously Presented) A system for creation of an opening of controllable format
2 through a layer of insulation material, comprising:

3 means for creating an opening through a layer of etch resist material provided
4 over the surface of a layer of insulating material having been deposited over the surface
5 of a substrate;

6 means, including a feedback mechanism, for obtaining a critical dimension
7 measurement of said opening created through said layer of etch resist material and
8 assuring that said critical dimension measurement is within design specification, said
9 feedback mechanism communicating with said means for creating an opening through a
10 layer of etch resist material to control said critical dimension measurement of said
11 opening;

12 means for creating an opening having non-linear sidewalls through said layer of
13 insulation material by applying a high-polymer based etch to the surface of said layer of

Appl. No. 10/661,793
Amdt. dated 04/01/2008
Response to Office action of 01/03/2008

Attorney Docket No.: TS01-1037
N1085-90149

14 insulation material, whereby a diameter of opening having non-linear sidewalls is
15 dependent on a diameter of said opening created through said layer of etch resist
16 material; and
17 means, including a feedback mechanism, for assuring that said opening created
18 through said layer of insulation material is within design specification.

1 16. (Previously Presented) A system for creation of an opening of controllable format
2 through a layer of insulation material, comprising:
3 means, including a feedback mechanism, for creating an opening through a layer
4 of etch resist material provided over the surface of a layer of insulating material having
5 been deposited over the surface of a substrate, such that the opening has a critical
6 dimension measurement that is within design specification, said feedback mechanism
7 communicating with said means for creating an opening through a layer of etch resist
8 material to control said critical dimension measurement of said opening;
9 means for creating an said opening through said layer of insulation material,
10 whereby a diameter of said layer of insulation material is dependent on a diameter of
11 said opening created through said layer of etch resist material; and
12 means, including a feedback mechanism, for assuring that said opening created
13 through said layer of insulation material is within design specification.

1 17. (Previously Presented) The system of claim 16, wherein said means,
2 including a feedback mechanism, for creating an opening, include means for making
3 corrections to an original critical dimension measurement that is not within design
4 specification.